## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:		)	Group Art Unit:
	Fumikatsu UESAWA	)	Examiner:
Application No.		)	
Filed:		)	
For:	Method of Manufacturing a	)	
	Semiconductor Apparatus with	)	
	Tapered Aperture Pattern to Form a	)	
	Predetermined Line Width	)	

Mail Stop Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## PRELIMINARY AMENDMENT PURSUANT TO 1.53(b)

Dear Sir:

Prior to substantively examining the instant application, please enter the following amendments.